2023년 2월 15일(수), 10:45-12:30

Room A (에메랄드 I, 5층)

D. Thin Film Process Technology 분과
[WA2-D] Growth Characteristics of Atomic Layer Deposition

좌장: 최병준 교수(서울과학기술대학교), 송봉근 교수(홍익대학교)

WA2-D-1 **10:45-11:00**	**A Study on the Characteristics of $Hf_{0.5}Zr_{0.5}O_2$ Thin Films Prepared by Direct and Remote Plasma Atomic Layer Deposition for the Application to Ferroelectric Memory** Da Hee Hong, Jae Hoon Yu, Won Ji Park, and Hee Chul Lee *Department of Advanced Materials Engineering, Tech University of Korea*
WA2-D-2 **11:00-11:15**	**ALD Deposited Ferroelectric ZrO_2 on Ru with Low Thermal Budget** Myeongchan Ko, Soyun Joo, Seungbum Hong, and Kyung Min Kim *KAIST*
WA2-D-3 **11:15-11:30**	**Advanced Atomic Layer Deposition (ALD): Ultrathin Metal Film Growth Using Discrete Feeding Method and Electric Potential Assisted ALD** Ji Won Han[1], Hyun Soo Jin[1], Yoon Jeong Kim[1], Ji Sun Heo[1], Woo-Hee Kim[1], Ji-Hoon Ahn[1], Jeong Hwan Kim[2], and Tae Joo Park[1] *[1]Department of Materials Science and Chemical Engineering, Hanyang University, [2]Department of Advanced Materials Engineering, Hanbat National University*
WA2-D-4 **11:30-11:45**	**Advanced Atomic Layer Deposition: Metal Oxide Thin Film Growth Using the Discrete Feeding Method** Jae Chan Park[1], Chang Ik Choi[1], Sang-Gil Lee[2], Seung Jo Yoo[2], Ji-Hyun Lee[2], Jae Hyuck Jang[2], Woo-Hee Kim[1], Ji-Hoon Ahn[1], Jeong Hwan Kim[3], and Tae Joo Park[1] *[1]Department of Materials Science and Chemical Engineering, Hanyang University, [2]Center for Research Equipment, KBSI, [3]Department of Advanced Materials Engineering, Hanbat National University*
WA2-D-5 **11:45-12:00**	**Multicomponent $HfZrO_x$ Thin Films through Atomic Layer Modulation** Ngoc Le Trinh[1], Chi Thang Nguyen[1], Bonwook Gu[1], Byungchan Lee[1], Sehee Kim[2], Kun Yang[3], Min Hyuk Park[3], Bonggeun Shong[2], and Han-Bo-Ram Lee[1] *[1]Department of Materials Science and Engineering, Incheon National University, [2]Department of Chemical Engineering, Hongik University, [3]Department of Materials Science and Engineering, Seoul National University*
WA2-D-6 **12:00-12:15**	**Atomic Layer Deposition of Ru Thin Film Using a Newly Synthesized Precursor with Open-coordinated Ligands** Seung Hoon Oh[1,2], Hyeonbin Park[1,3], Tae Joo Park[2], Taeyong Eom[1], and Taek-Mo Chung[1,4] *[1]Thin Film Materials Research Center, KRICT, [2]Department of Materials Science and Chemical Engineering, Hanyang University, [3]Department of Materials Science and Engineering, KAIST, [4]Department of Chemical Convergence Materials, University of Science and Technology (UST)*
WA2-D-7 **12:15-12:30**	**Atomic Layer Deposition of Zinc Oxide and Aluminum Oxide Using Alcohols as the Oxygen Source** Miso Kim[1], Euncheol Shin[2], Hyewon Song[2], Jin-Ha Hwang[2], and Bonggeun Shong[1] *[1]Department of Chemical Engineering, Hongik University, [2]Department of Materials Science and Engineering, Hongik University*